Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L10	11317	(polysilicon or conductive) and plug and ("hard mask" or SiN or mask$4)	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/28 09:03
L11	2318	(polysilicon or conductive) same plug same ("hard mask" or SiN or mask$4)	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/28 08:53
L12	16225	(SAC or "self aligned contact")	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/28 08:03
L13	225	11 and 12	USPAT; USOCR	OR	OFF	2005/03/28 08:03
L20	2	"6277727".pn.	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/28 08:42
L21	401	(polysilicon or conductive) same plug same ("hard mask" or SiN)	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/28 08:54
L22	1923	(polysilicon or conductive) and plug and ("hard mask" or SiN) and (contact or via) and etch$4	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/28 09:05
L23	216	(polysilicon or conductive) same plug same ("hard mask" or SiN) same (contact or via) same etch$4	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/28 09:23
L26	233	(polysilicon or conductive) same plug same ("hard mask" or SiN) same (contact or via or trench) same etch$4	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/28 09:24
L27	7293	(polysilicon or conductive) and plug and ("hard mask" or SiN or "silicon nitride") and (contact or via or trench)	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/28 09:25
L28	686	27 and 12	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/28 09:25
L29	23	lee-sung-kwon.in.	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/28 09:25

L30	12	kim-sang-ik.in.	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/28 09:26
L31	2	sun-jun-hyeub.in.	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/28 09:27